

# Spin-on-Glass As-200

<b>Elements of Interest</b> Si, O, As	<b>Key Element atoms/cm<sup>3</sup></b> As, 4E+21	<b>Key Element % in Film</b> Arsenic
<b>Viscosity (cps)</b> 1.1 cps <b>Refractive Index (n)</b> @635nm 1.49	<b>Thickness</b> Coats 250 nm at 3000 rpm	<b>Shelf Life</b> 20°C 3 months 4°C 9 months

## Benefits

- Medium Arsenic doping level
- Uniform Coatings
- High purity materials
- Stable processing independent of flow rates
- Available with impurity specification of less than 1 ppm or less than 50 ppb

## Typical Application

This is a standard silicate arsenic doped glass very typical for semiconductor applications. It begins curing at about 200°C to give a less dense but solid film. It continues to become increasingly dense as temperatures increase to 650°C or higher. We recommend baking at the highest temperature the material will see in any post processing. For doping applications the glass is often removed after drive in.

## Packaging

- 240ml
- 500ml
- 1 l
- 2.5 l
- 4 l

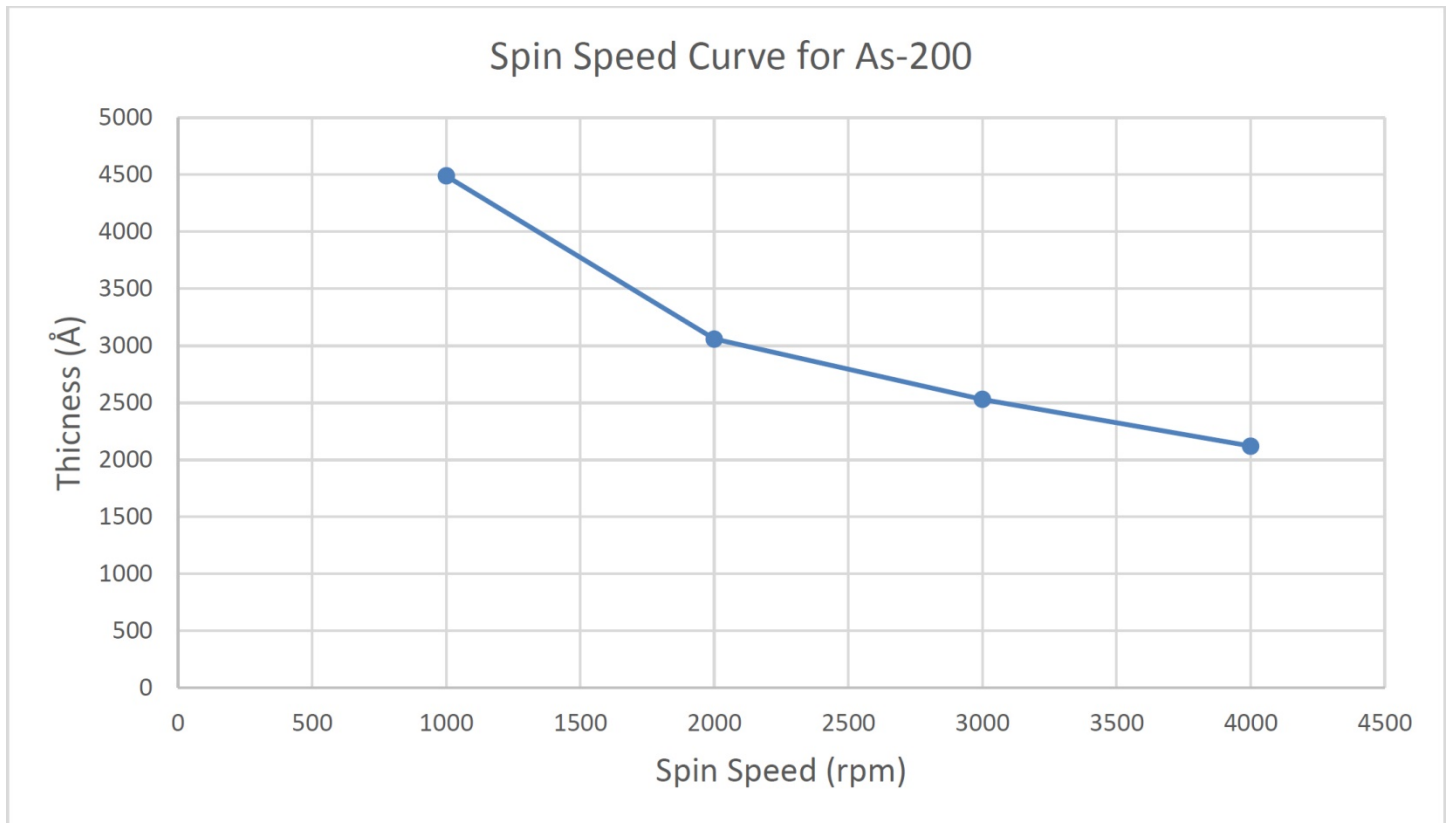
## Alternative Products

As-300

## Elements Available to Add

- Sb
- Bi
- Blends of two or more elements
- Other elements available for compound semiconductor use

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